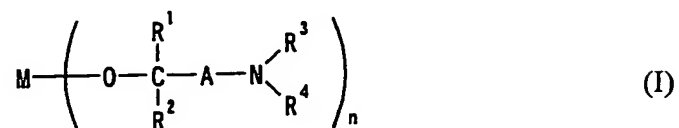


ABSTRACT

A metal compound represented by general formula (I):



wherein R¹, R², R³, and R⁴ each represent an alkyl group having 1 to 4 carbon atoms; A
 5 represents an alkanediyl group having 1 to 8 carbon atoms; M represents a lead atom, a
 titanium atom or a zirconium atom; n represents 2 when M is a lead atom or 4 when M
 is a titanium or zirconium atom. The metal compound has a low melting point and is
 therefore deliverable in a liquid state, has a high vapor pressure and is therefore easy to
 vaporize, and, when mixed with other metal compound, undergoes no denaturation due
 10 to a chemical reaction. The metal compound is suitable as a material of thin film
 formation processes involving vaporization of a metal compound, such as CVD.